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## Design and fabrication of single electron spin qubits in lithographically defined silicon quantum dots

Y. P. Lin<sup>1</sup>, M. K. Husain<sup>1</sup>, F. M. Alkhalil<sup>1</sup>, H. M. H. Chong<sup>1</sup>, A. J. Ferguson<sup>2</sup>, H. Mizuta<sup>13</sup>

<sup>1</sup>School of Electronics and Computer Science, University of Southampton, Highfield, Southampton, SO17 1BJ U.K.

<sup>2</sup>Microelectronics Research Centre, Cavendish Laboratory, JJ Thomson Avenue, Cambridge, CB3 0HE U.K.

<sup>3</sup>School of Material Science, JAIST, Nomi, Ishikawa, 923-1292, Japan

Electron spins in Si quantum dots (QDs) provide an attractive alternative to their GaAs conterparts due to their much longer spin relaxation times[1]. We realise a pair of SOI-based double quantum dot (DQD) transistors facing each other with only a 50nm separation via E-Beam lithography and high resolution HSQ resist. A VLSI compatible fabrication process is implemented allowing for future scalability in quantum systems. We propose a new method of single electron detection verified by Monte-Carlo based simulations making use of the periodicity in the charge stability diagram of a DQD.

[1] C. B. Simmions et al., Phys. Rev. Lett. 106, 156804 (2011).

	Invited Talk	Yun Peng Lin
	Prefer Contributed Oral Presentation	ypl1g10@ecs.soton.ac.uk
X	Prefer Poster Presentation	

Topic: Charges and spins